

(19)



JAPANESE PATENT OFFICE

PATENT ABSTRACTS OF JAPAN

(11) Publication number: **60079724 A**(43) Date of publication of application: **07.05.85**

(51) Int. Cl.

H01L 21/30**F16B 2/00****H01L 21/306**(21) Application number: **58186712**(71) Applicant: **HITACHI LTD**(22) Date of filing: **07.10.83**(72) Inventor: **KUMADA SHIGETO**(54) **ROTARY PROCESSING DEVICE**

COPYRIGHT: (C)1985,JPO&Japio

(57) Abstract:

PURPOSE: To prevent the scattering of a sample from a placing stand by a method wherein a mechanism, with which the sample will be fixed or supported, is provided on the circumferential part of the sample-placing stand utilizing the centrifugal force generated when said placing stand is rotated.

CONSTITUTION: A mask 1 is placed on a placing stand 6, and when the placing is completed, said placing stand 6 which is connected to a rotary shaft 5 is rotated by driving a motor 13. With the rotation of the placing stand 6, the fixing pawl 11 provided at the upper part is rotated in the center direction of rotation by the centrifugal force which works on the weight 12 provided on the lower part of a pendulum 9. When the placing stand 10 reaches certain rotating speed, the fixing pawl 11 comes in contact with the non-patterned part (edge part) located on the upper surface of the mask 1, pressed from the direction of the upper surface of the mask 1, and the mask 1 can be fixed before it is scattered.

